



Docket No.: 3811-0122P  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Yi LYU et al.

Application No.: 10/621,380

Confirmation No.: 4059

Filed: July 18, 2003

Art Unit: 1712

For: SILOXANE-BASED RESIN AND  
METHOD FOR FORMING INSULATING  
FILM BETWEEN INTERCONNECT  
LAYERS IN SEMICONDUCTOR  
DEVICES BY USING THE SAME

Examiner: M. G. Moore

**AMENDMENT AFTER FINAL ACTION (37 C.F.R. SECTION 1.116)**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated May 2, 2005, finally rejecting claims 1 and 3-13, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 7 of this paper.